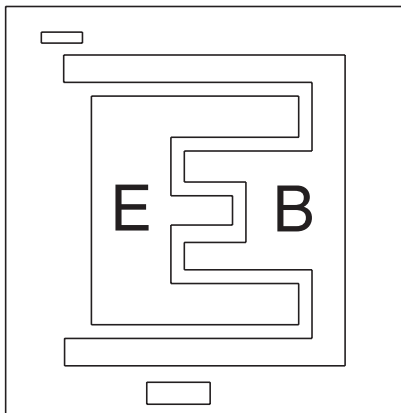


PROCESS DETAILS

Process	EPITAXIAL PLANAR
Die Size	31.5 x 31.5 MILS
Die Thickness	11 MILS
Base Bonding Pad Area	7.8 x 6.2 MILS
Emitter Bonding Pad Area	8.0 x 5.3 MILS
Top Side Metalization	Al - 12,000Å
Back Side Metalization	Au - 10,000Å

GEOMETRY



BACKSIDE COLLECTOR R0

GROSS DIE PER 4 INCH WAFER

11,380

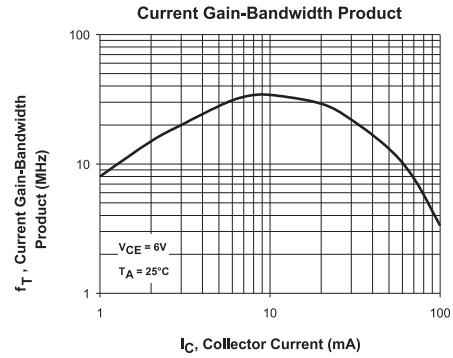
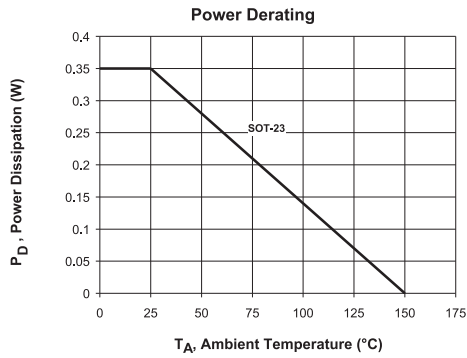
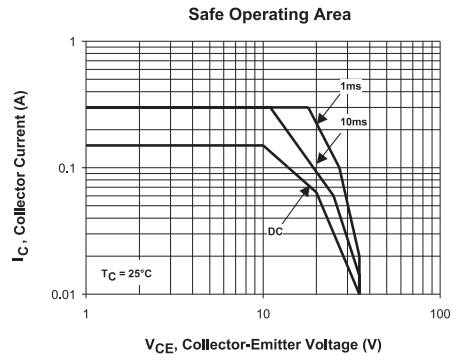
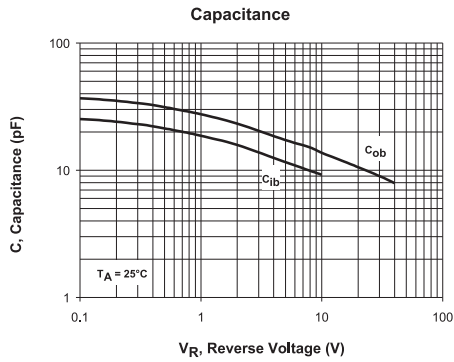
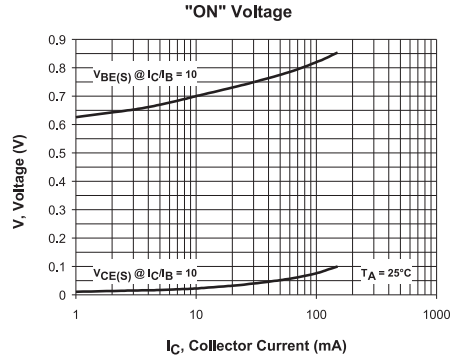
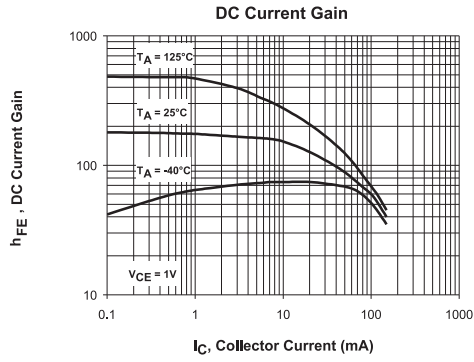
PRINCIPAL DEVICE TYPES

CMPT404A

MPS404A

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R2 (1-August 2002)



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